

Docket No.: M4065.0531/P531-A

(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Examiner: Walter Lee Lindsay Jr.

Werner Juengling, et al.

Allowed: August 23, 2005

Application No.: 10/673,362

Group Art Unit: 2879

Filed: September 30, 2003

For: REVERSE METAL PROCESS FOR CREATING A METAL SILICIDE TRANSISTOR GATE STRUCTURE

APPLICANTS' COMMENTS ON EXAMINER'S STATEMENT OF REASONS FOR ALLOWANCE

Commissioner for Patents MS: Issue Fee P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Applicants agree only in part with the Examiner's reasons for allowance in that the prior art of record fails to disclose the limitations noted by the Examiner. However, the Examiner's statement does not reflect all of the language of each of the allowed claims. The totality of the language of each claim provides reasons for the allowance of each claim.

Dated: November 17, 2005

Respectfull submitted.

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